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APPLICANT : TOSHIBA CORP;

INVENTOR : JINNO KIYOKATSU;

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TITLE : METALLIC PATTERN FORMING METHOD

ABSTRACT : PURPOSE: To form a desired metallic pattern on a semiconductor substrate by removing desired parts of a tetrafluoroethylene film, by an etching process using a photoresist, formed on the substrate on which various kinds of elements have been formed and then vacuum depositing a metal.

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